



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: >90%CA
3. SURFACE QUALITY(S1,S2): 40/20(S/D)
4. WAVEFRONT ERROR(RMS): $\lambda/4@633\text{ nm}$ (SUBSTRATE)
5. PARALLELISM(S1,S2): <3 arcmin
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:
 FILTERING(S1): $T_{\text{avg}} > 90\%$, $T_{\text{abs}} > 85\% @ 380-475\text{ nm}$, 45° AOI
 $R_{\text{avg}} > 95\%$, $R_{\text{abs}} > 90% @ 505-800\text{ nm}$, 45° AOI
 AR COATING(S2): $R_{\text{abs}} < 2% @ 380-475\text{ nm}$, 45° AOI

DRAWING PROJECTION			LBTEK			
	NAME	DATE	DM10-490SP			
DRAWN	LZHOU	JUL./30th/24	SHORTWAVE DICHOIC MIRROR $\phi 25.4\text{ mm} \times 3.2\text{ mm}$, 490 nm			
APPROVAL	WCHENG	JUL./30th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	3.6 g	2:1	A